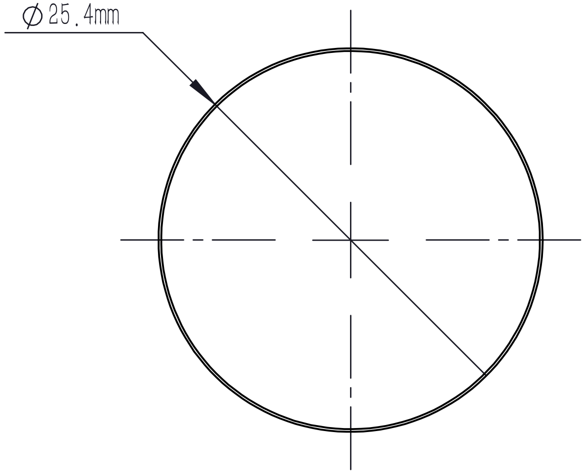

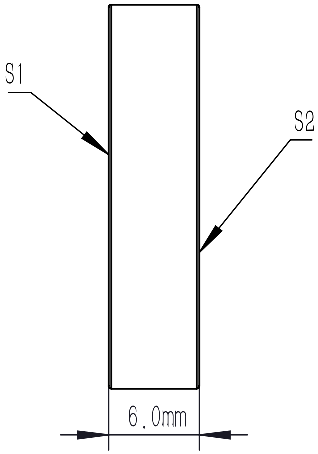

NOTES

1. COATING(S1)：HIGH ENERGY LASER LINE COATING
   Rs,Rp>99%@532 nm&1064 nm,0° -45° AOI
2. CLEAR APERTURE(S1)：>85%CA
3. SURFACE QUALITY(S1)：40/20(S/D)
4. SURFACE FLATNESS(S1)：λ/10@633 nm
5. PARALLELISM(S1,S2)：<3 arcmin
6. CHAMFER：<0.2 mm,45°
7. THICKNESS TOLERANCE：±0.2 mm
8. DIAMETER TOLERANCE：+0/-0.1 mm
9. OTHER SURFACES：FINE GROUND
10. DAMAGE THRESHOLD：8J/cm^2,532 nm,10 ns,20 Hz；
    30J/cm^2,1064 nm,10 ns,20 Hz；

DRAWING PROJECTION			LBTEK			
	NAME	DATE	LPM10-532-1064-HP			
DRAWN	LZHOU	Aug./5th/24	HIGH ENERGY LASER LINE MIRROR ∅25.4 mm×6.0 mm,532-1064 nm			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	6.7 g	2:1	A